

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|------------------|
| L1 | 122 | immersion adj (liquid apparatus lithography medium) and @ad<"20040122" and "355"/\$.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/27 14:50 |
| S4 | 1 | tbutoxyl adj acrylate | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/26 10:58 |
| S5 | 288 | polymer and immersion adj lithography | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/26 11:02 |
| S6 | 2 | silicon adj polymer and immersion adj lithography | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/26 11:08 |
| S7 | 59 | polymer with immersion adj lithography | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/26 13:17 |
| S11 | 56 | polymer with immersion adj (liquid apparatus lithography) and @ad<"20040122" | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/26 13:44 |
| S13 | 4 | polymer same immersion adj (liquid apparatus lithography medium) and @ad<"20040122" and "355"/\$.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/12/27 09:41 |